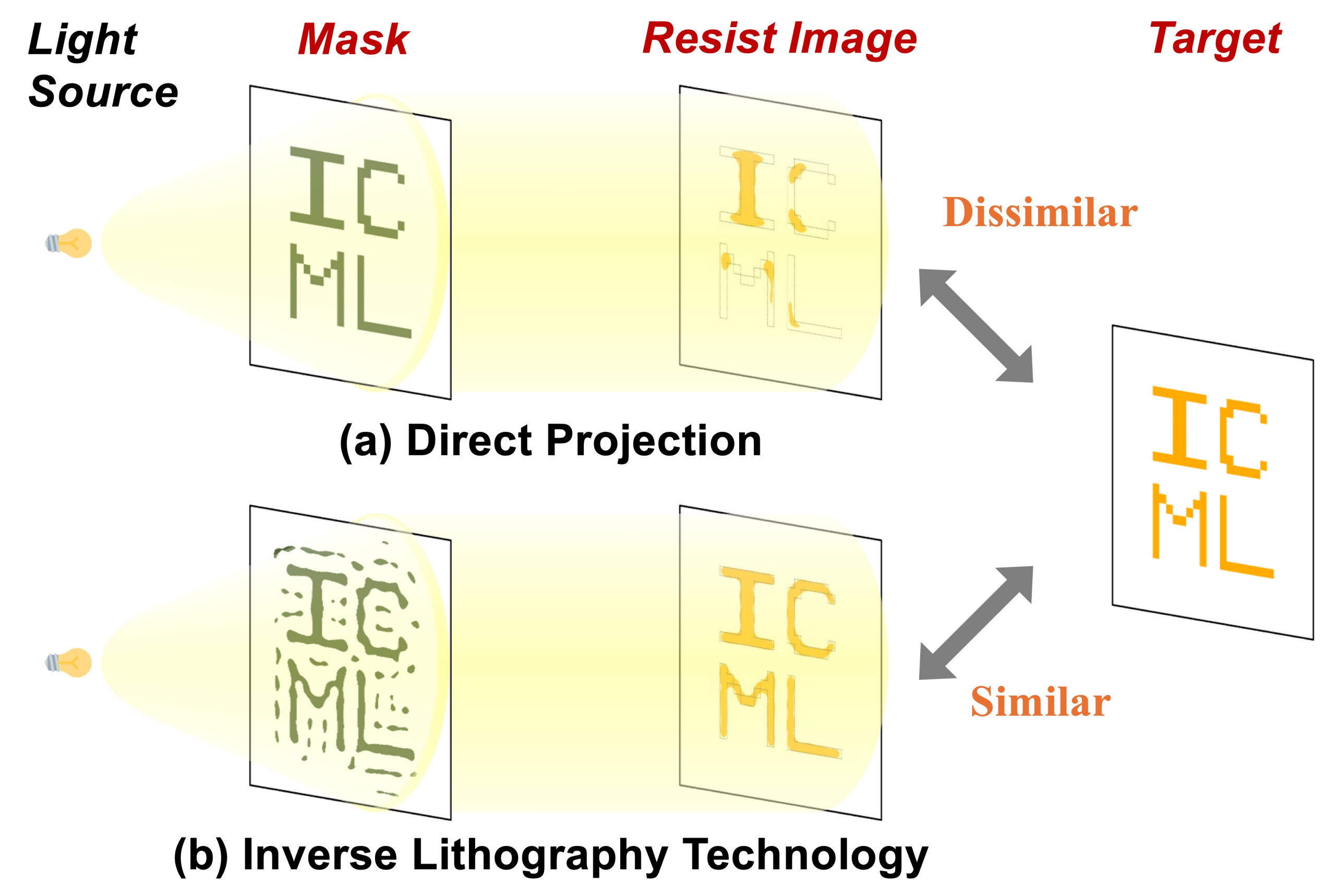


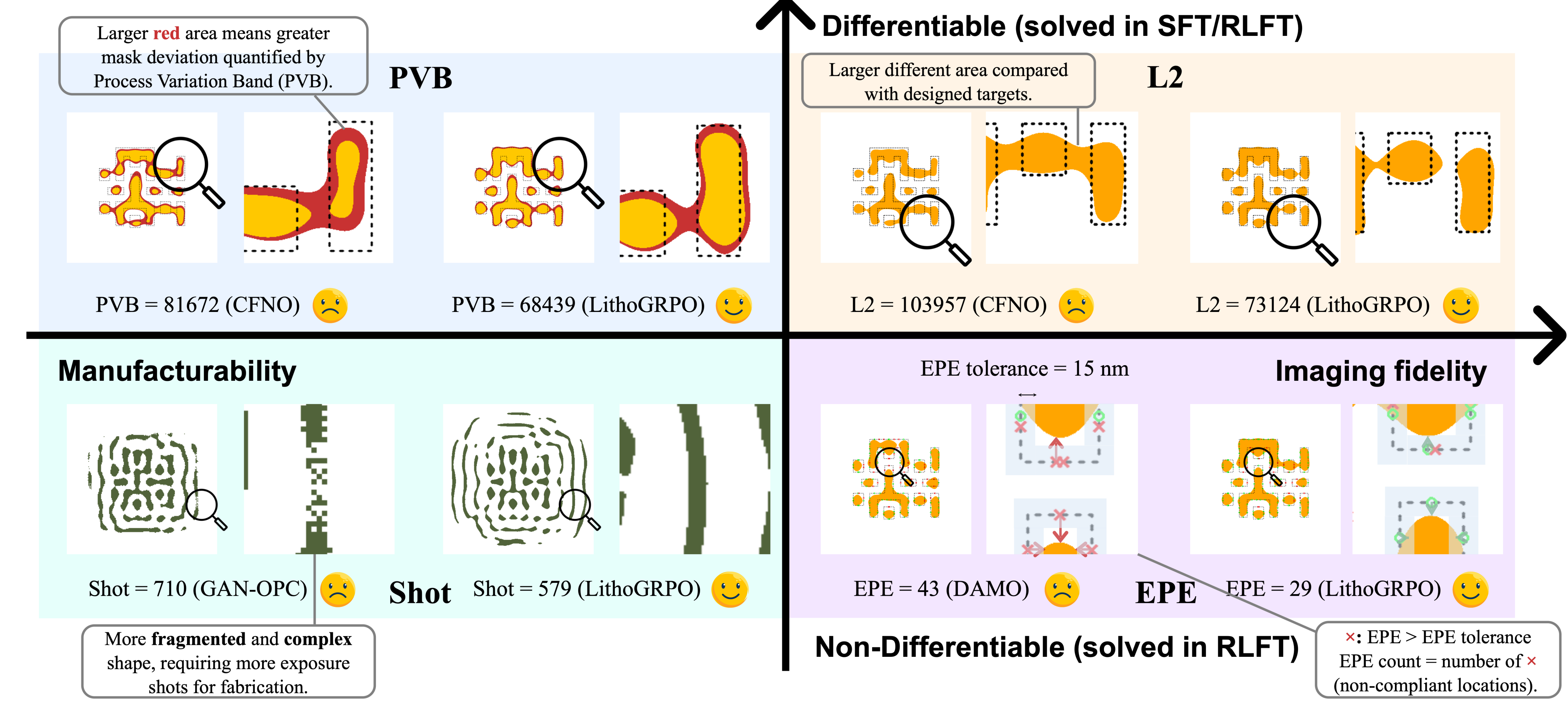
Background

Inverse Lithography Technology (ILT) is the task of **generating a 2D mask** whose printed pattern, after optical lithography, matches the target layout.



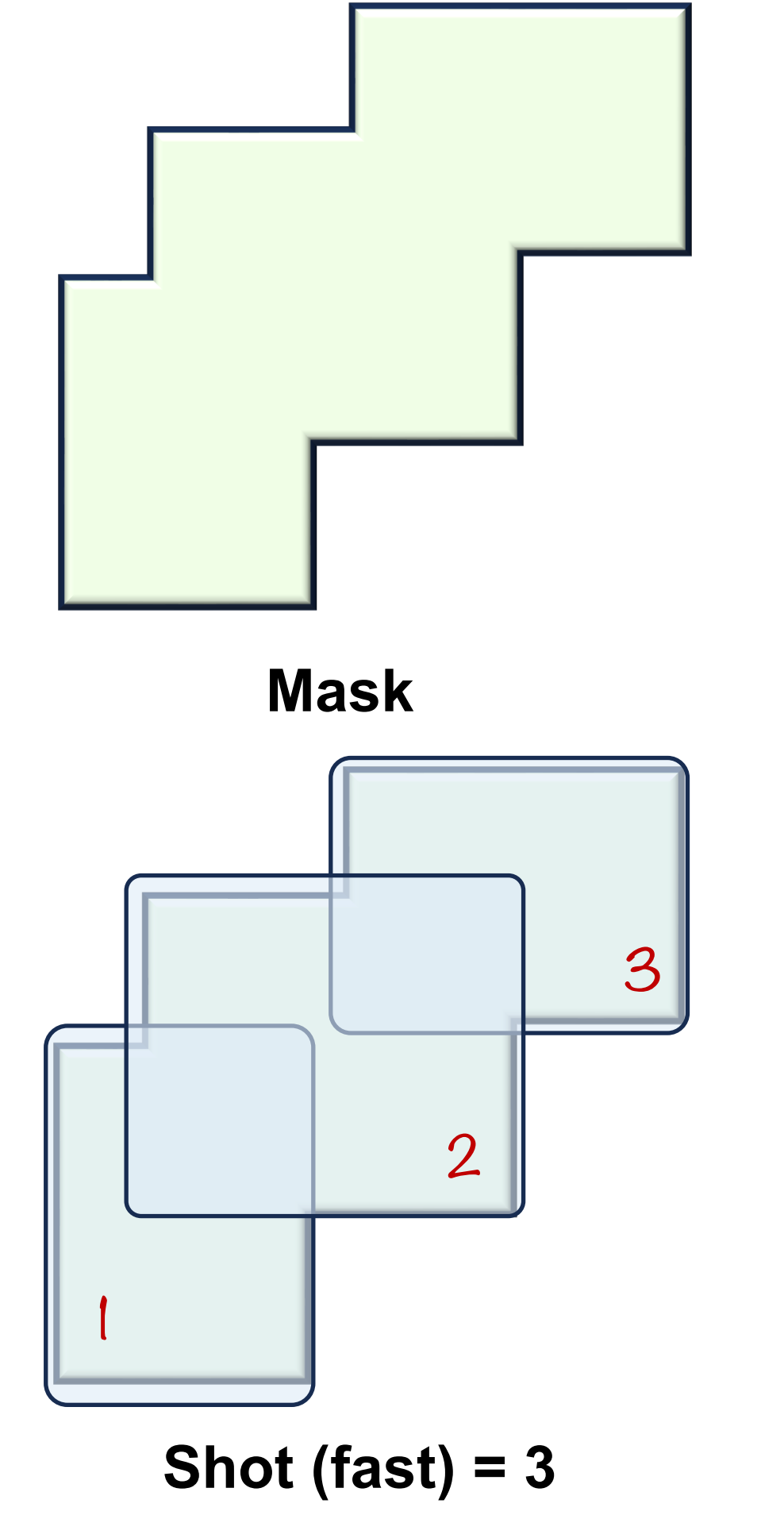
Evaluation Metrics

Four metrics evaluate ILT quality: **differentiable** L2/PVB are optimized in **SFT**, while **non-differentiable** EPE/Shot are handled by **RLFT**.



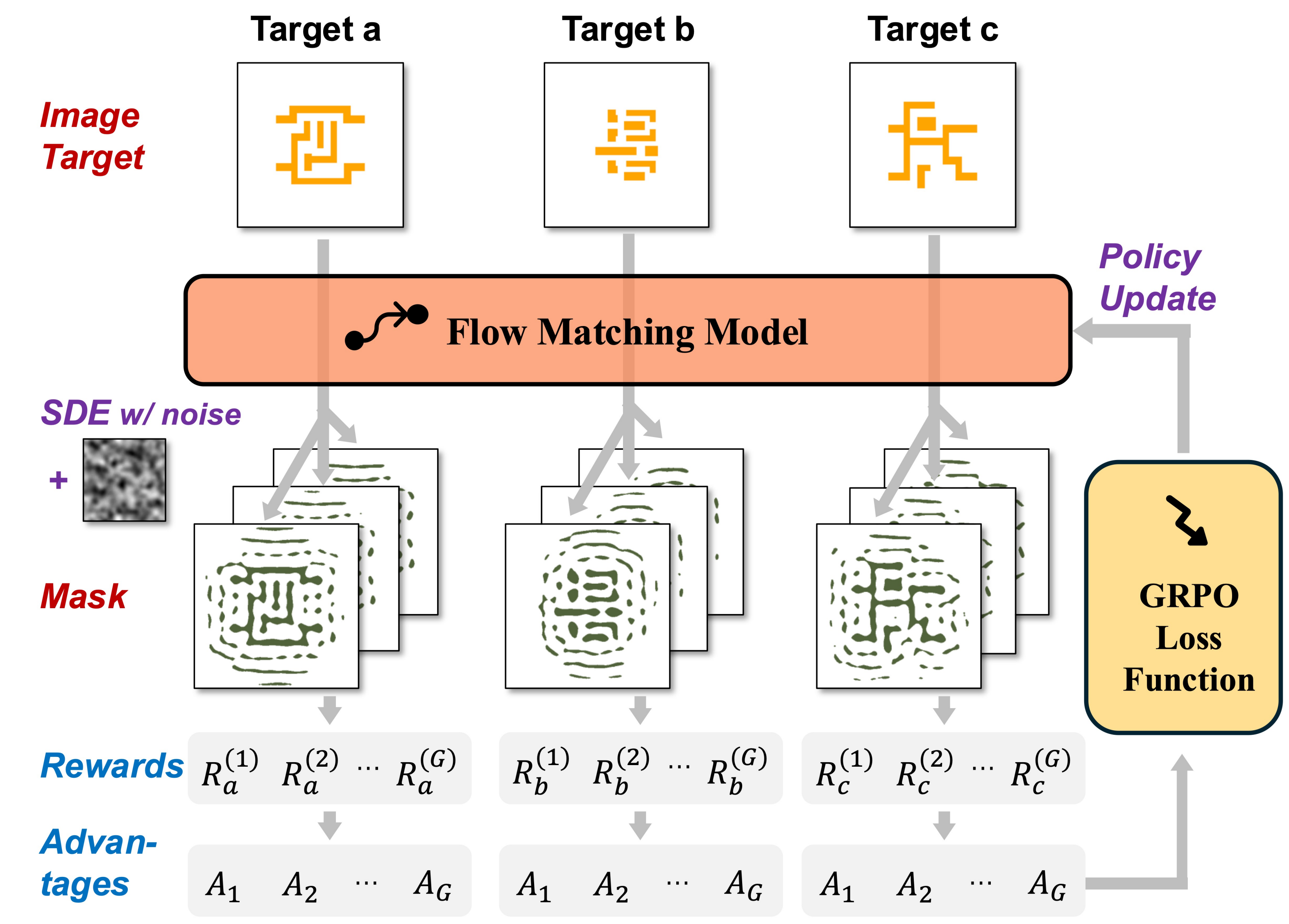
Method – Fast Shot Count

Shot counting via a **minimum set-cover ILP** with overlapping rectangles, 130x faster.



Method – Flow Matching w/ GRPO

A flow-matching model generates **mask groups** per target, optimized end-to-end by GRPO using **metric-based rewards**.



Experimental Results

LithoGRPO attains the **strongest overall metric trade-off** among all methods.

Light Source

Lens

Mask $\times$

Lens

Aerial Image
 $I = h(\mathbf{x})$

Resist Image
 $Z = g(\mathbf{x}), g \triangleq f \circ h$

PV Band (PVB)

Minimal Contour

Max-Min Range (PVB)

GAN-OPC

Neural-ILT

CFNO

DAMO

LithoGRPO (Pretrain)

LithoGRPO (SFT)

LithoGRPO (RLFT)

L2

EPE

PVB

Shot

42133

2

50625

562

41953

2

50499

581

56562

4

59985

362

35141

1

54838

550

37656

0

55820

480

31280

0

49382

840

32620

0

49627

461

Links

